

ABSTRACT

A method for forming small, isolated device structures by photolithography, utilizing overlapping bi-layer suspension-bridge shaped photomasks. The use of a suspended mask to define a device shape beneath it eliminates the problems associated with uneven undercutting of the usual bi-layer mask which is a stencil portion formed on a lower pedestal. In particular, the use of a suspended mask eliminates undesirable dielectric buildup around the device caused by an insufficiently undercut pedestal or of premature mask lift-off caused by an overly undercut pedestal.